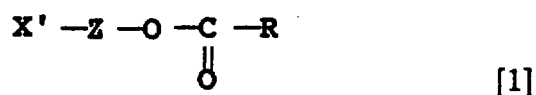


# ABSTRACT OF THE DISCLOSURE

## A NOVEL MONOMER AND A POLYMER OBTAINED THEREFROM

This invention relates to a monomer shown by the general formula [1]



5 (wherein X' is a cyclic hydrocarbon residue containing polymerizable double bond(s), which may have a substituent, Z is a spacer or a direct bond and R is a substituted alkyl or alkenyl group having one or two protected hydroxyl groups as substituent) and a polymer containing a segment derived from the above monomer.

The said polymer is useful for a resist composition, etc. utilized in the  
10 production of semiconductor elements, etc. and the said monomer is useful as a starting material for the polymer, and a resist composition using the said polymer can remarkably advantageously be used as a resist material for ArF excimer laser beams which has been considered to be a valuable technology for exposure belonging to the coming generation.